

Information Disclosure
Statement By Applicant

(Use Several Sheets if Necessary)

Atty Docket No.

KLA1P012

Applicant:

LEE

Filing Date

Herewith

Application No.:

Unassigned

Group

Unassigned

JC932 U.S. PTO
09/695726

10/23/00

U.S. Patent Documents

Examiner Initial	No.	Patent No.	Date	Patentee	Class	Sub-class	Filing Date
	A	4,162,528	07/24/79	Maldonado et al.			03/31/78
	B	4,476,386	10/09/84	Reid et al.			06/10/81
	C	4,534,049	08/06/85	Koga			08/10/83
	D	4,675,889	06/23/87	Wood et al.			07/08/85
	E	4,777,364	10/11/88	Sartore			06/15/87
	F	4,885,465	12/05/89	Nagatsuka et al			07/05/88
	G	4,959,848	09/25/90	Parobek			12/16/87
	H	5,055,679	10/08/91	Ninomiya et al.			01/03/90
	I	5,065,020	11/12/91	Kanda			11/20/90
	J	5,299,252	03/29/94	Takahashi			04/07/93
	K	5,350,921	09/27/94	Aoyama et al.			07/23/93
	L	5,485,499	01/16/96	Pew et al.			08/05/94
	M	5,530,732	06/25/96	Takemi			05/19/95
	N	5,596,195	01/21/97	Obori et al.			09/15/95
	O	5,656,812	08/12/97	Takahashi			07/19/96
	P	5,657,363	08/12/97	Hossain et al.			10/10/95
	Q	5,754,620	05/19/98	Hossain et al.			09/13/96
	R	5,777,336	07/07/98	Silver et al.			10/03/95
	S	5,866,903	05/09/97	Morita et al.			05/09/97
	T	5,892,809	04/06/99	Wittry			09/08/98
	U	5,060,247	10/22/91	Watanabe			11/15/89
Examiner				Date Considered			12-16-61

Examiner: Initial citation considered. Draw line through citation if not in conformance and not considered. Include copy of this form with next communication to applicant.

**Form 1449 (Modified)****Information Disclosure
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Other Documents

Examiner Initial	No.	Author, Title, Date, Place (e.g. Journal) of Publication
<i>AK</i>	V	J.L. Pouchou and F. Pichoir, "Electron Probe X-Ray Microanalysis Applied To Thin Surface Films and Stratified Specimens", Scanning Microscopy, Supplement 7., (1993), pp. 167-189.
	W	"High-Resolution X-ray Microanalysis for Low Voltage Applications", NORAN INSTRUMENTS, (1997), 5 pages
	X	M. Stavrev ^a , D. Fischer ^a , C. Wenzel ^a , and T. Heiser ^b , "Study OF Ta(N,O) diffusion barrier stability: analytical and electrical characterization of low level Cu contamination in Si", MICROELECTRONIC ENGINEERING, 37/38 (1997) pp. 245-251
	Y	JeanLouis Pouchou, "X-Ray microanalysis of stratified specimens", Elsevier Science Publishers B.V., Analytica Chimica Acta. 283 (1993) pp. 81-97
	Z	Schiebl et al., "A characteristic fluorescence correction factor for use in electron probe microanalysis", Microsc. Microanal. Microstruct. 2, 1991, pp. 413-423
	AA	S. Sevov et al., "A comparison of recently developed correction procedures for electron probe microanalysis", Scanning , 1989, vol. 11, pp. 123-134
	BB	August et al., "A method for determining the mass thickness of thin films using electron probe microanalysis", Scanning, 1987, vol. 9, pp. 145-155
<i>KG</i>	CC	August et al., "Energy distribution of electrons transmitted through thin foils", Institut fur Angewandte aund Technische Physik, Technische Universitat Wien Wiedner Hauptstr.8-10, A-1040 Wien (Vienna), Austria
Examiner		Date Considered <i>12-17-01</i>

Examiner: Initial citation considered. Draw line through citation if not in conformance and not considered. Include copy of this form with next communication to applicant.

Form 1449 (Modified)

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Other Documents

RF	DD	Pfeiffer et al., "Models and their implementation", CEC-Vienna Reports, No. 92-08, December, 1992.
	EE	"MuFilm Data Collection & K-Ratio Measurement Documentation", pp. 2-10
	FF	August et al., "Calculation and Comparison of the Surface Ionization", Institut fur Angewandte und Technische Physik, Technische Universitat Wien, Wiedner Hauptstr. 8-10, A-1040 Wien (Vienna), Austria
	GG	August et al., "Calculation and Comparison of the Backscattering Factor R for Characteristic X-Ray Emission", Scanning, 1988, vol. 10, pp. 107-113
	HH	August et al., "The Backscattering Factor as a Part of the Correction Procedures Employed in Quantitative Electron Probe Microanalysis", Radex-Rundschau, 1988, pp. 624-637.
	II	August et al., "Calculation of the electron backscattering coefficient for thin films using a simple electron scattering model", J. Microsc. Spectrosc. Electron., 1989, vol. 14, pp. 189-201.
KF	JJ	August, et al., "Theoretical prediction of the electron backscattering coefficient for multilayer structures", Journal of Microscopy, February 1990, vol. 157, pp. 247-254.

Examiner

Date Considered

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